

Table of Contents

	<i>Page</i>
Foreword	iii
Program	v
Officers and Committee Chairmen 1959-60	vi
Founder Members and Life Members	vii
The President's Receiving Line	viii
Symposium Notes	ix
Officers and Committee Chairmen 1960-1961	x
Dr. Ira H. Abbott—Guest Speaker	xiii

TECHNICAL PROGRAM

VACUUM SYSTEM COMPONENTS

Bakeable Molecular Pumps—J. W. Beams	1
Vacuum Pumping with a Bladed Axial-flow Turbomachine—Charles H. Kruger and Ascher H. Shapiro	6
A New Design for Ultra-high Vacuum Valves—James Wishart and George H. Bancroft	13
Ultra-high Vacuum Components for the Proposed Stanford Two Mile Linear Electron Accelerator—David J. Goerz, Jr.	16
A Large Bakeable Ultra-high Vacuum Valve—W. B. Parker and J. T. Mark	21
Non-refrigerated Isolation Traps for Ultra-high Vacuum Systems—Manfred A. Biondi	24
A Small Ionic Pump Employing Metal Evaporation—E. V. Kornelsen	29
Improved Elastomer Seal Designs for Large Metal Ultra-high Vacuum Systems Permitting Ultimate Pressures in the Low 10^{-10} Torr Range—Imre Farkass and E. J. Barry	35
Evaluation of a New Fluoroelastomer as a Gasketing Material for High Vacuum Systems—R. R. Addis, Jr., L. Pensak and Nancy J. Scott	39
Stabilized Air Pumping with Diode Type Getter-Ion Pumps—Robert L. Jepsen, Arthur B. Francis, Sherman L. Rutherford and Burdell E. Kietzmann	45
Getter-Ion Pumps using Cartridge Evaporators—T. Pauly, R. Welton and R. B. Herb	51
Design and Performance of Modern Diffusion Pumps—M. H. Hablanian and A. A. Landfors	55
A Graphical Determination of Vacuum Chamber Pumpdown Time—Charles H. Naundorf	60
A Molecular Sieve Trap for Use at 10^{-9} Torr—David J. Goerz	65

Table of Contents

VACUUM MEASURING TECHNIQUES

	<i>Page</i>
Studies on the Blears Effect at Pressure Measurements in the Ultra-high Vacuum Range—R. A. Haeffer and J. Hengevoss	67
A High Vacuum Gauge Calibration System—Wallace S. Kreisman.....	75
A Laboratory Leak Detector Using an Omegatron—Edward H. Nicollian.....	80
Control of Deposition Rate and Film Thickness with the Crystal Oscillator—K. H. Behrndt and R. W. Love	87
A Photomultiplier Ion Gauge—H. Riemersma, R. E. Fox and W. J. Lange	92
A Hot-cathode Magnetron Ionization Gauge for the Measurement of Ultra-high Vacua—J. M. Lafferty	97
Measurement of Helium and Neon by Means of an Ionization Gauge—E. A. Wenzel and L. T. Loh	104

PANEL DISCUSSION: PRESSURE MEASUREMENTS—THEIR APPARATUS AND TECHNIQUES

Lower Pressure Limit of Common Gauges—Helmut Schwarz. ¹	
Errors in the Measurement of Pressure with Ionization Gauges—P. A. Redhead ..	108
The Influence of Absorption and Desorption on Measurements of Low Pressures—G. Reich	112
A Detailed Examination of the Principles of Ion Gauge Calibration—Wayne B. Nottingham and Franklin L. Torney, Jr.....	117
Present Status of Standardization and Calibration of Vacuum Gauges—Ivory P. S. Fish	123

INDUSTRIAL AND METALLURGICAL APPLICATIONS OF VACUUM

The Efficiencies of Ideal and Actual Ejectors—David L. Fiske	125
Operating Experiences with Steam Ejector Vacuum Pumps on Vacuum Melting Installations—P. S. Lewis, Jr., M. A. Orehoski and V. V. Fondrk	131
An Evaporator for the Controlled Deposition of Alloy Films over Large Substrate Areas—K. H. Behrndt	137

¹ This manuscript arrived too late for inclusion in these *Transactions* and will be published elsewhere.

Table of Contents

	<i>Page</i>
Gas Determination in Vacuum Tube Materials—B. J. Bliss	145
Thermal Degassing of Materials—Peter F. Varadi	149
Vacuum System Requirements for Electrical Space Propulsion Engines—Peter E. Jasper.....	155
Nasa Electric Rocket Test Facilities—Thomas A. Keller	161

VACUUM SYSTEMS

Problems in the Construction and Operation of Bakeable and Non-Bakeable Vacuum Systems—L. Holland	168
High Pumping Rate Vacuum Systems—W. W. Balwanz, J. R. Singer and N. P. Frandsen	182
Ultra-high Vacuum Demountable System for Mass Spectrometer Gas Analysis—David Lichtman and A. Hebling	187
A Versatile Ultra-high Vacuum System for Thin Film Research—C. Robert Meissner	196
Some Characteristics of Vacion Pumped High Vacuum Systems—M. Rivera, R. Zaphiropoulos and D. Harra	206
Discussion on Optimization of Large Oil Pumped Ultra-high Vacuum Systems—N. Milleron and L. L. Levenson	213

VACUUM SYSTEM APPLICATIONS

Methods of Electron Bombardment Heating for Deposition of Metallic Thin Films—J. P. Reames	219
Control of Final Water Content in Freeze-dried Substances—J. D. Mellor	224
Gas-metal Reactions in Oxygen at Low Pressures—T. N. Rhodin and L. H. Rovner	228
A New Apparatus for Low Pressure Gas Analysis—A. Lench and G. S. Martin....	238
Sublimation of Materials in Vacuum—Kenneth A. Ray.....	243
Pumping Speeds of Sorption Pumps—P. F. Varadi and K. Ette	248

THIN FILMS

X-ray Diffraction Studies of Crystal Orientations in Thin Films—Dorothy A. Brine and R. A. Young	250
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	<i>Page</i>
An Auto-recording Mechanism for Assay of Ultra-thin, Radioactive Vacuum Condensed Films—Luther E. Preuss and Claude Bugenis	260
Resistance Change due to Adsorption—Yoshihiko Mizushima	273
A Torsion Microbalance for Operation in Ultra-high Vacua—H. Mayer, W. Schroen and D. Stünkel	279
The Sputtering of Solid Surfaces with Positive Ions—S. P. Wolsky and E. J. Zdanuk	282
Sputtering of Metals and Semiconductors by Neon Ions with Energies from 50 to 600 eV—N. Laegreid and G. K. Wehner	286
Sputtering at Very Low Ion Energies—Robley V. Stuart and G. K. Wehner	290
Clean Substrates for Evaporated Permalloy Films—S. Nielsen	293
Formation and Study of Thin Ferrite Films—E. Banks, N. H. Riederman, H. W. Schleuning and L. M. Silber	297
Silicon Monoxide Evaporation Techniques—Carl E. Drumheller	306
The Simultaneous Vacuum Evaporation of Two Component Systems—D. S. Campbell and H. Blackburn	313
Studies on the Vacuum Deposition of the Low Melting Temperature Glass System of Arsenic, Sulfur and Thallium—Philip S. McDermott and Eugene R. Stack ..	319
Method of Measuring and Controlling Evaporation Rates During the Production of Thin Films in Vacuum—Helmut Schwarz	326
Resonance Frequency Shift Thin Film Thickness Monitor—Stanley J. Lins and Harley S. Kukuk	333
 PUMPING MECHANISMS	
A Study of the Mechanism of Inert Gas Ion Pumping—G. Carter and J. H. Leck	339
High Temperature Gettering Processes—E. I. Doucette	347
Some Fundamental Problems in Dynamic Sorption Measurements—Paolo Della Porta and Franco Ricca	352
Re-emission Studies of Ionically Pumped Gases—R. E. Fox and J. S. Knoll	364
Optimization of Molecular Flow Conductance—Leonard L. Levenson, Norman Milleron and Donald H. Davis	372
Simulation of Space Environment—Willard H. Bennett	378
On Pumping Mechanisms in Getter-Ion Pumps Employing Cold-cathode Gas Discharges—S. L. Rutherford, S. L. Mercer and R. L. Jepsen	380

Table of Contents

	<i>Page</i>
PARTIAL PRESSURE MEASURING DEVICES	
Distillation with Least Mixing : The Microfractor—Part I—K. Hickman	383
The Microfractor—Part II Experimental—W. H. Hogan and K. Hickman ..	389
The Farvitron—A New Partial Pressure Indicator without Magnetic Field—G. Reich	396
Some Examples of the Use of the Farvitron for Plotting Rapidly Changihg Pro- cesses—W. Bächler and G. Reich	401
The Operation of the r-f Mass Spectrometer at High r-f Voltage Levels—H. W. Ehlbeck, K. H. Loecherer, J. Ruf and H. J. Schuetze	407
A Sensitive High-Speed Mass Spectrometer for Ultra-high Vacuum Work—W. D. Davis and T. A. Vanderslice	417
Operational Data on the Omegatron as a Vacuum Analyzer—William R. Watson, Robert A. Wallace and Joseph Lech.....	421